

SuperPix0 Calibrations

Threshold Correction Study

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SuperPix0

- chip characterization in lab:
 - thr. dispersion & ENC computed in electrons *assuming a linear gain*:

chip	thr. disp. (e^-)	ENC (e^-)	gain (mV/fC)
12	460 ± 30	71 ± 1	37.3
19	500 ± 30	85 ± 1	38.7
53	520 ± 30	77 ± 1	38.6
54	500 ± 30	77 ± 1	39.2
55	580 ± 30	77 ± 1	36.9

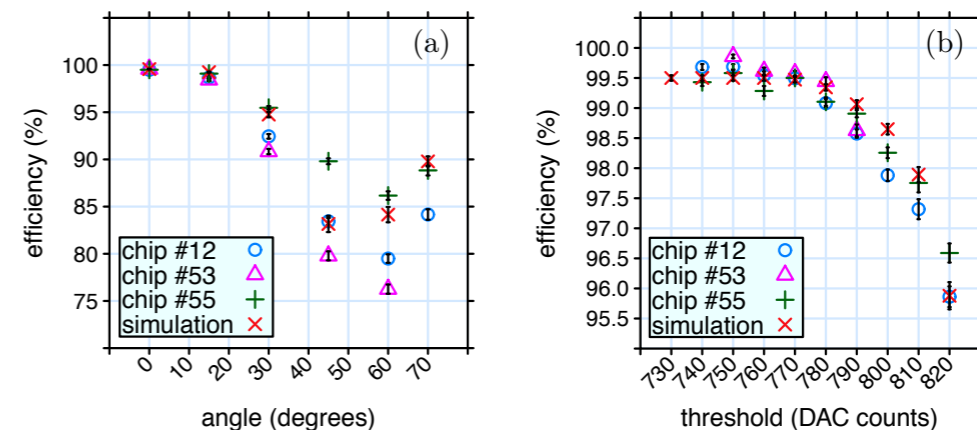
paper

Table 1: Lab characterization of the 5 chips tested during the test-beam.

- 2011 Testbeam:
 - scan in angle done with a threshold at **770** DAC, corresponding to 1/4 MIP *assuming a linear gain*:

Figure 9: Hit efficiency as a function of the angle of incidence of tracks when the pixel charge threshold corresponds to about 25% of a m.i.p. (left), and as a function of the threshold for normal-incidence tracks (right), for all detectors under test. The DAC values in the picture on the right correspond to a range from 12.5% to 40.6% of the charge released by a m.i.p. Monte Carlo expectations are also shown.

on 200 μm Si:
 1 MIP = 16k e^- = 2.6 fC
 1/4 MIP = 4k e^- = 0.65 fC



Gain Calibration

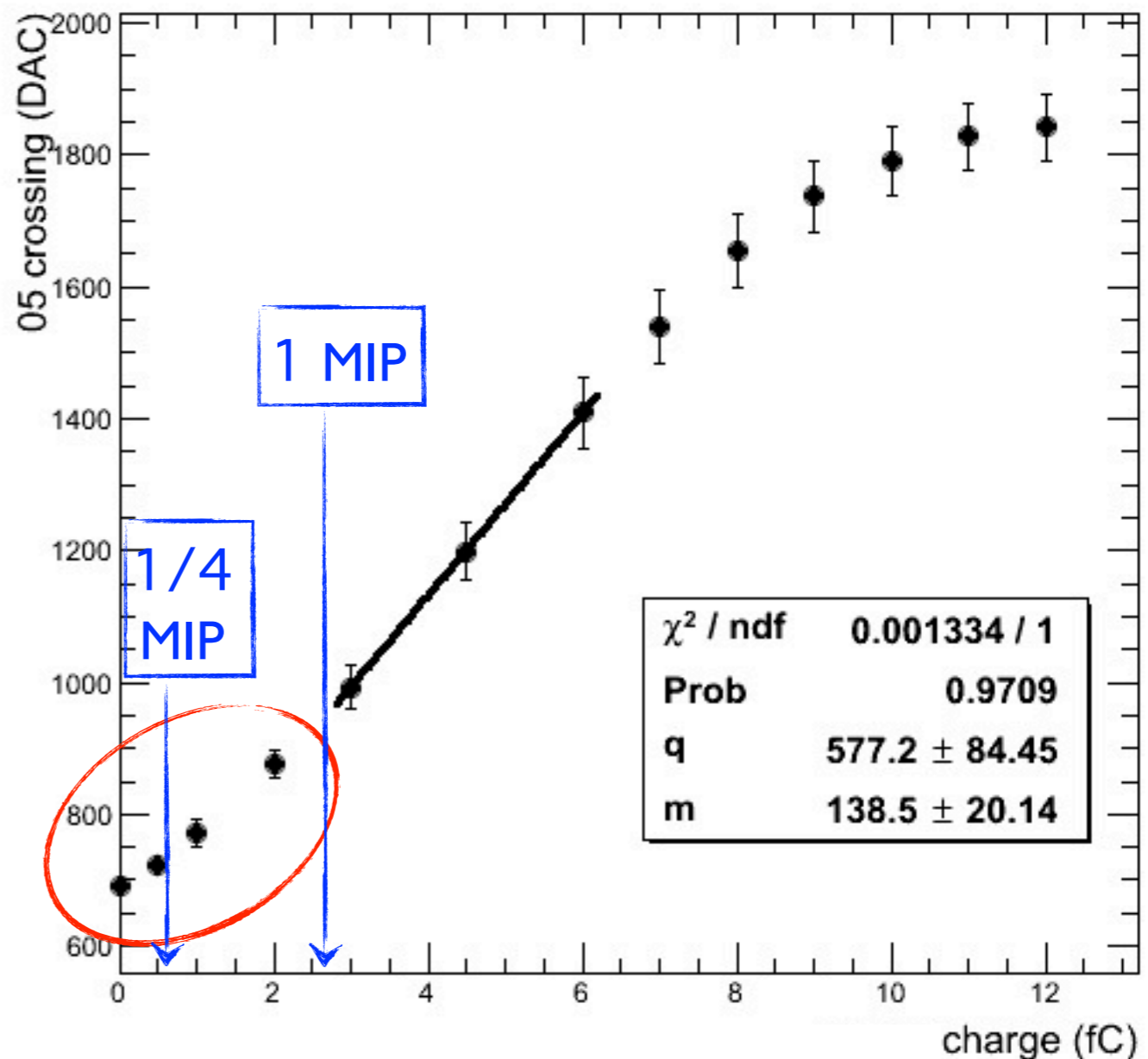
The gain for charges < 2.6 fC is not linear (due to a comparator malfunction):

- observed in chip I, ena20 (128 pixels)
- V_{out} = pre-ampl. output = voltage at 50% occupancy. V_{out} and baseline for each charge of each DUT is estimated as the average (over the enabled macrocolumns) of the mean of the distributions (of the pixels of a given macrocolumn)

we need to parameterize the gain at low injected charges to understand the threshold in terms of electrons

NOTE: DUTs are mounted on a different carrier and have been tested on a different board than chip I.

$V_{out}(q)$ for chip I:

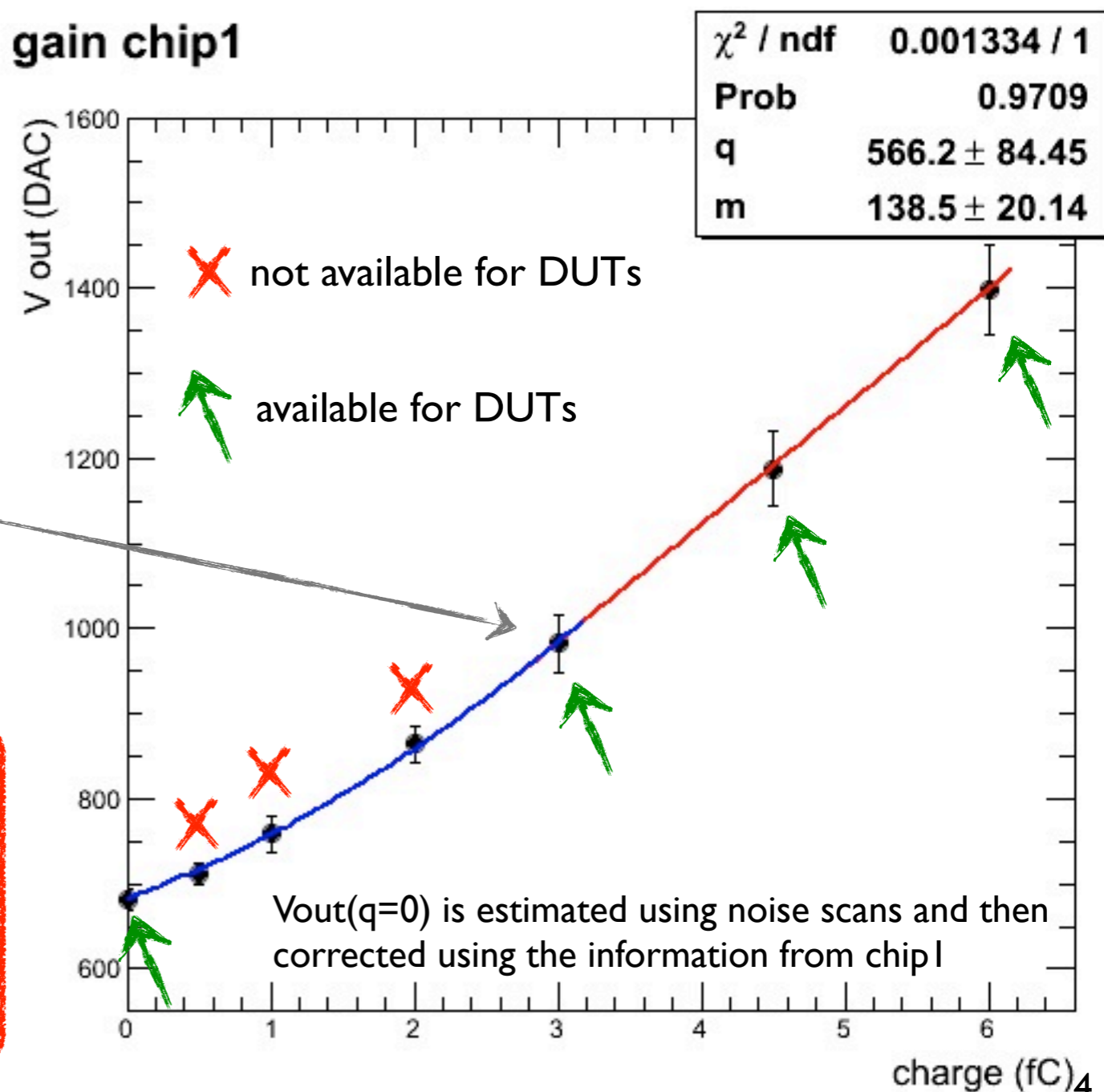


Procedure and Validation

1. define the curve $y(x)$ in 2 regions
 - linear region: $y(x) = mx+q$
 - non-linear region: $y(x) = ax^2 + bx + c$
2. fit the linear region and extract m (*old gain*)
3. find a, b, c such that:
 - $y(0) = V_{out}(q=0)$
 - the curve is continuous in $q'=3fC$
 - the derivative is continuous in $q'=3fC$
4. shift the curve so that $y(0) = \text{baseline}$

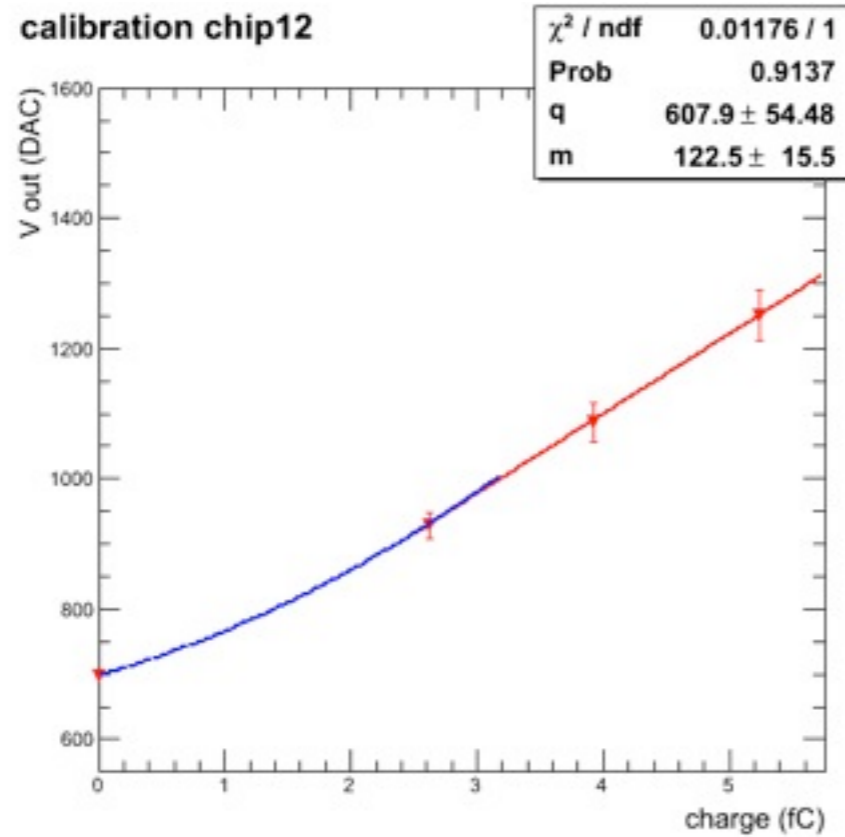
**Parameterization validated on chip I.
The calibration will be further
validated measuring V_{out} for $q < 2fC$
also for the DUTs**

gain chip1

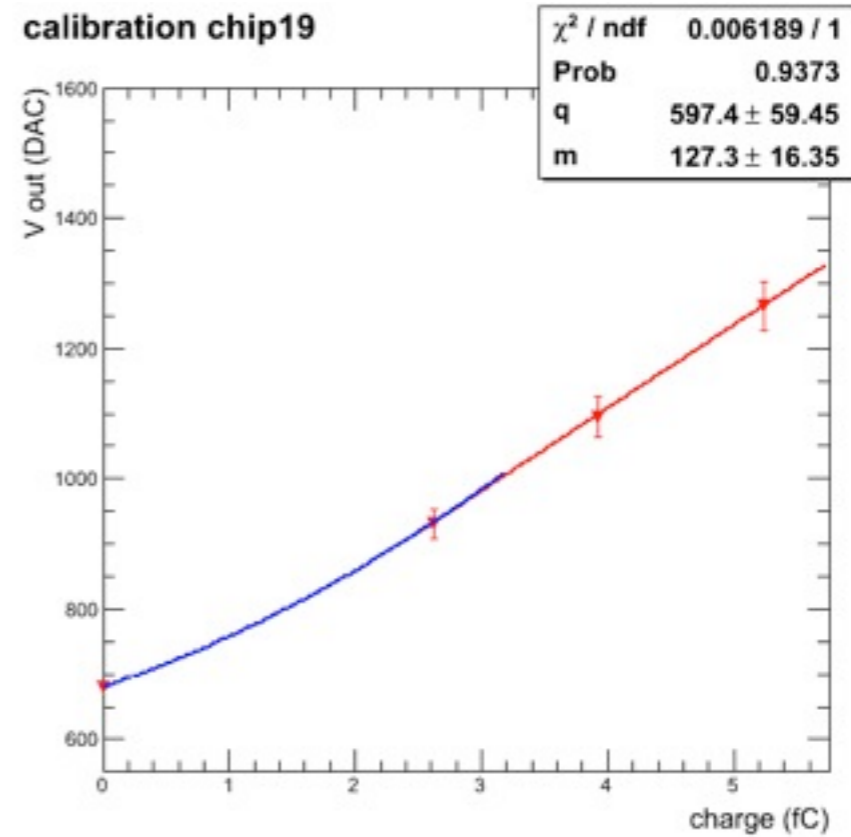


DUTs calibrations

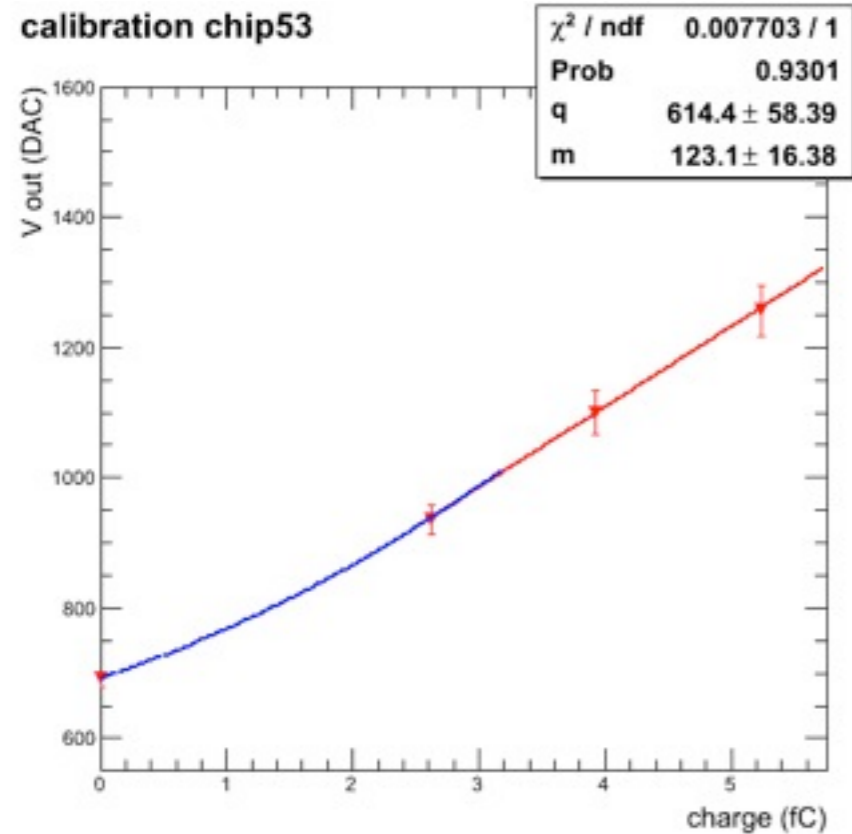
calibration chip12



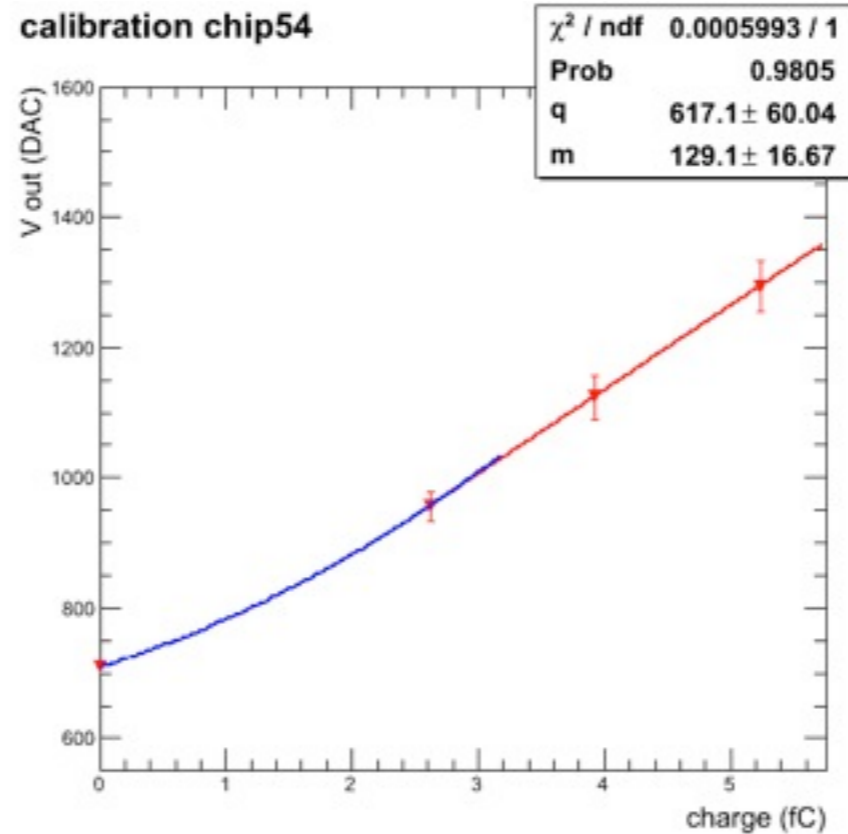
calibration chip19



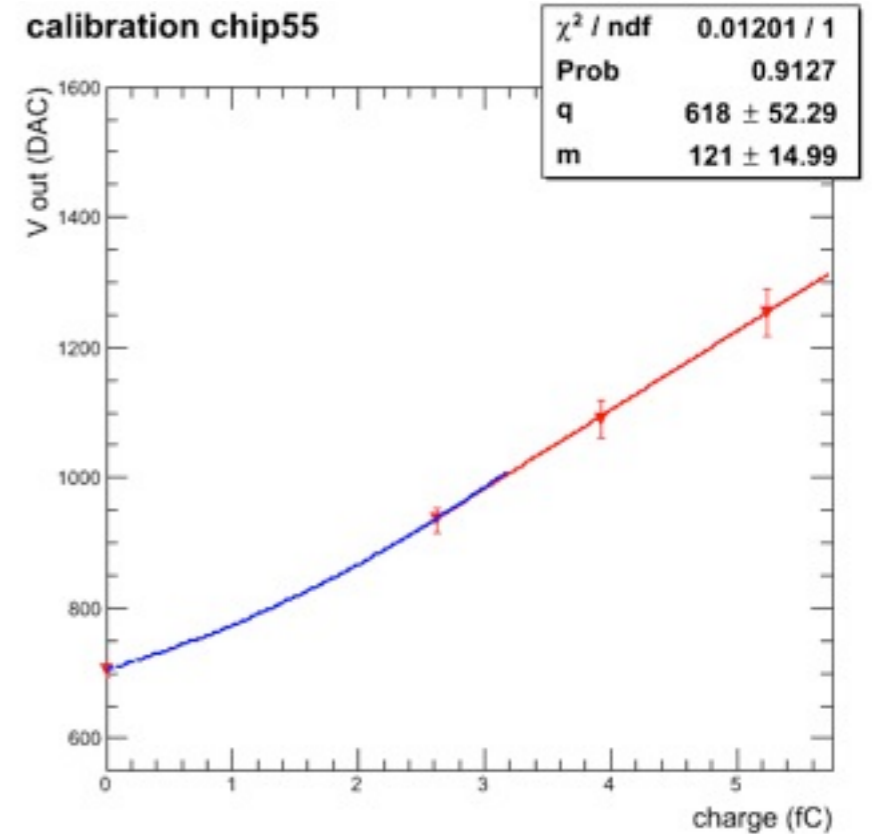
calibration chip53



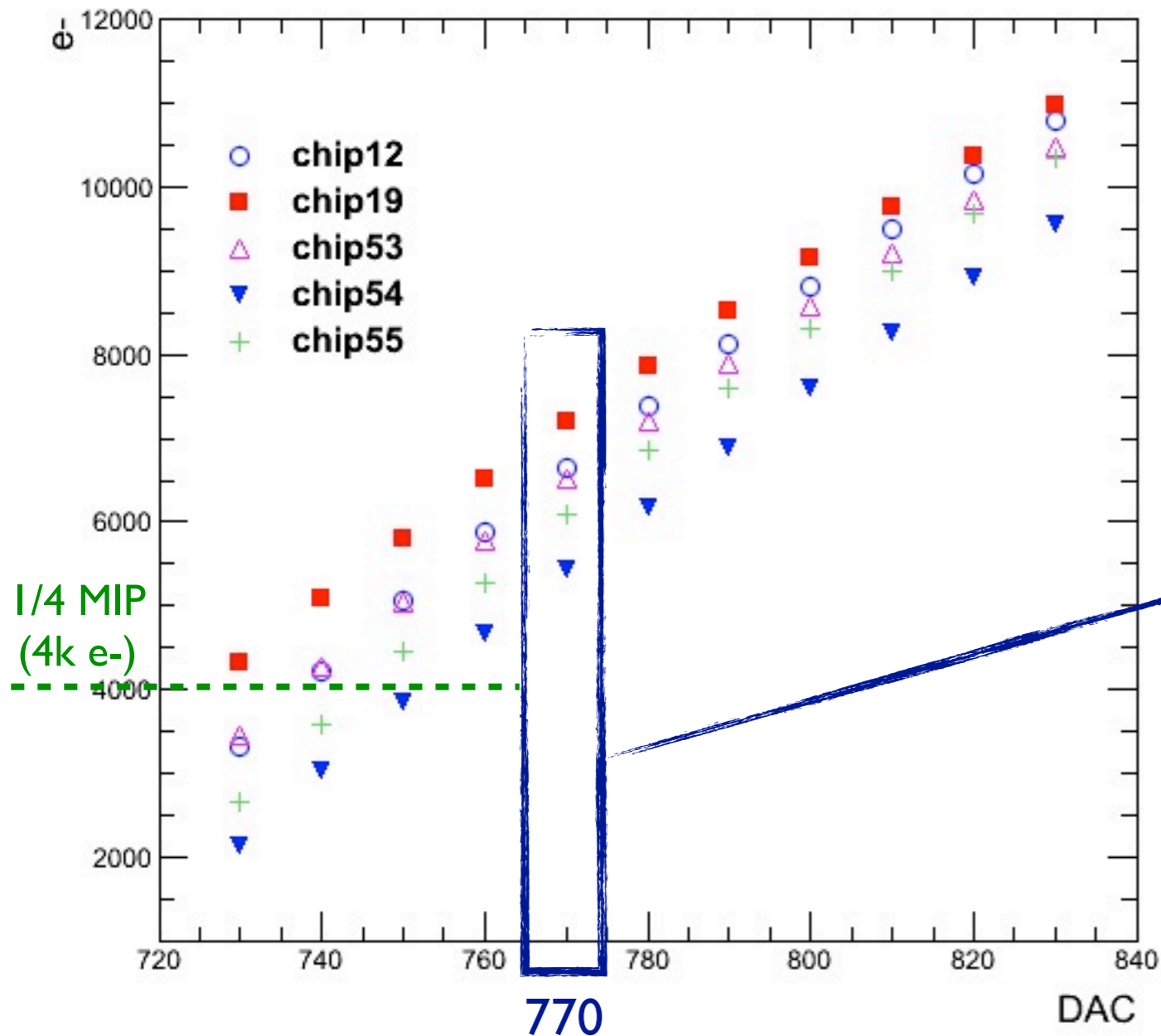
calibration chip54



calibration chip55



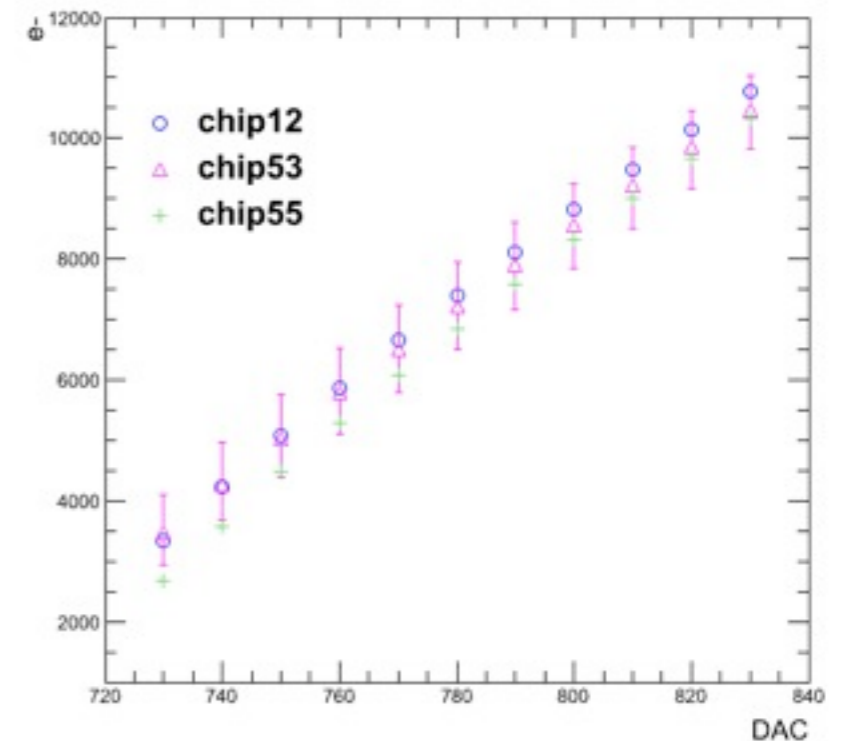
Threshold: from DAC to electrons



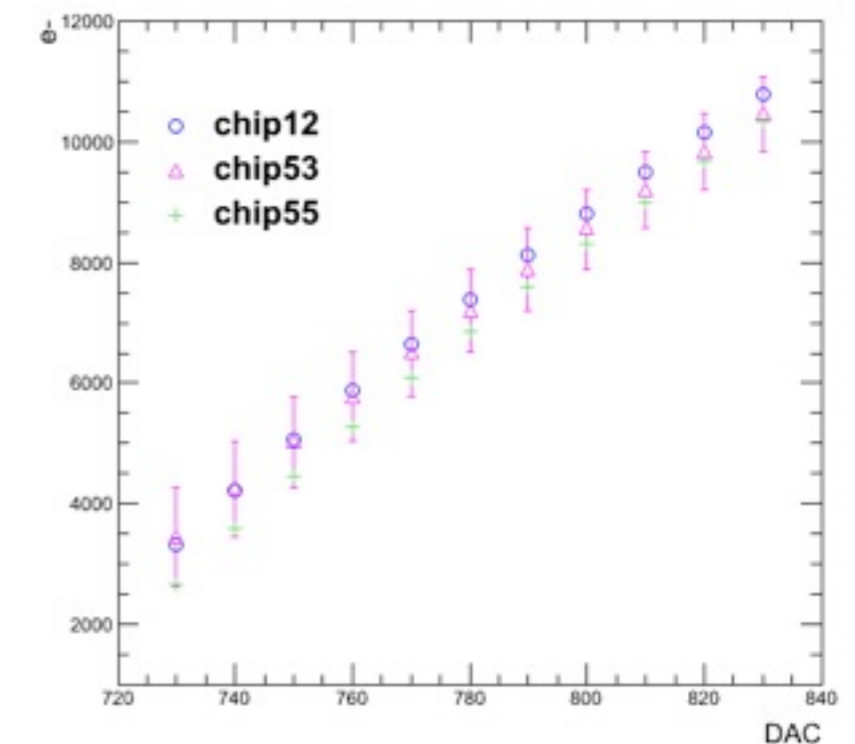
- the range of **730 – 820 DAC** corresponds to:
 - chip12 → 3340 – 10800 e- = 20.9% – 67.5% MIP
 - chip53 → 3460 – 10500 e- = 21.6% – 66.5% MIP
 - chip55 → 2670 – 10300 e- = 16.7% – 64.4% MIP
- the threshold of **770 DAC** corresponds to:
 - chip12 → 6650 e- = 41.6% MIP
 - chip53 → 6510 e- = 40.7% MIP
 - chip55 → 6090 e- = 38.1% MIP

Calibration Error Estimation

- vary the **gain** in the linear region by $\pm 1\sigma$ and repeat points 3. and 4. of the procedure in slide 4
- example from chip53:
 - error $\sim 520-740$ e- (19% to 5% relative error).



- vary the **baseline** by ± 1 RMS and repeat point 4. of the procedure in slide 4
- example from chip 53:
 - error $\sim 630-830$ e- (24% to 6% relative error).



ENC & thr. disp. re-evaluation

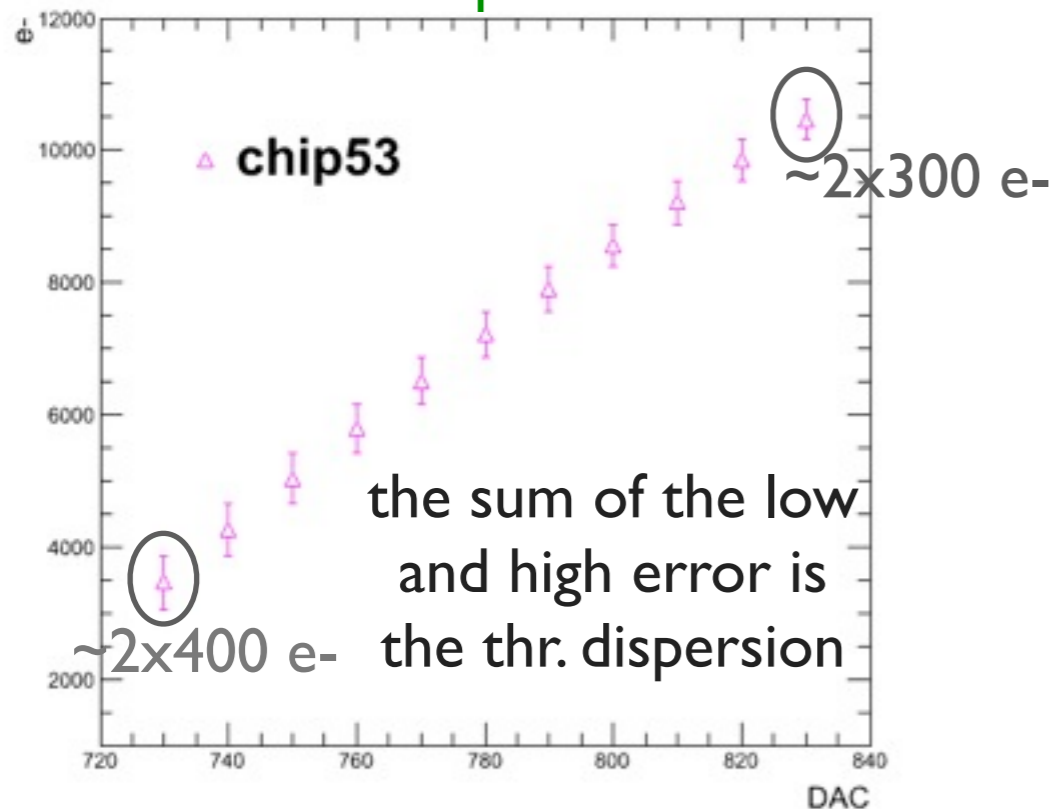
the value in mV is estimated as the RMS of the distribution of the baseline; need the equivalent in electrons to compare it to the noise. Since the gain depends on the threshold, the value of the threshold dispersion in electrons will also depend on the threshold:

currently reported on the paper (assuming linear gain):

chip	thr. disp. (e^-)	ENC (e^-)	gain (mV/fC)
12	460 ± 30	71 ± 1	37.3
19	500 ± 30	85 ± 1	38.7
53	520 ± 30	77 ± 1	38.6
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55	580 ± 30	77 ± 1	36.9

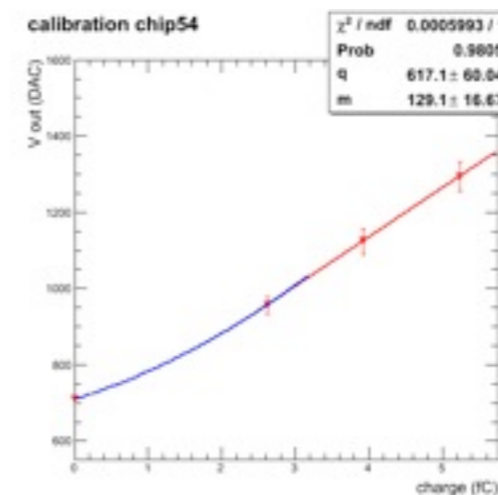
Table 1: Lab characterization of the 5 chips tested during the test-beam.

threshold dispersion:



current value is underestimated, re-evaluate it using the new calibrations:

quote the linear gain, not mentioning the non linearity at small charges



corrected ENC & thr. disp.

DUT	baseline (DAC)	baseline RMS (DAC)	thr. disp. (e-) at 770 DAC	ENC (DAC)	ENC RMS (DAC)	ENC (e-)	linear gain (mV/fC)
chip12	697	9	680	1.4	0.3	158 ⁺⁶⁰ ₋₃₅	37.4 ^{+4.7} _{-4.7}
chip19	679	10	674	1.7	0.3	164 ⁺⁵³ ₋₃₂	38.9 ^{+5.0} _{-5.0}
chip53	691	10	710	1.6	0.3	150 ⁺⁵⁰ ₋₃₁	37.6 ^{+5.0} _{-5.0}
chip54	708	10	750	1.6	0.5	163 ⁺⁶¹ ₋₃₅	39.5 ^{+5.0} _{-5.0}
chip55	704	11	860	1.5	0.3	166 ⁺⁵⁹ ₋₃₅	36.9 ^{+4.5} _{-4.5}

NOTE: quoted errors correspond to variations on linear gain^{+1 σ} _{-1 σ}

currently reported on the paper (assuming linear gain):

chip	thr. disp. (e ⁻)	ENC (e ⁻)	gain (mV/fC)
12	460 ± 30	71 ± 1	37.3
19	500 ± 30	85 ± 1	38.7
53	520 ± 30	77 ± 1	38.6
54	500 ± 30	77 ± 1	39.2
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now in agreement with post-layout simulations (150 e-)

Table 1: Lab characterization of the 5 chips tested during the test-beam.

Corrections to the Paper

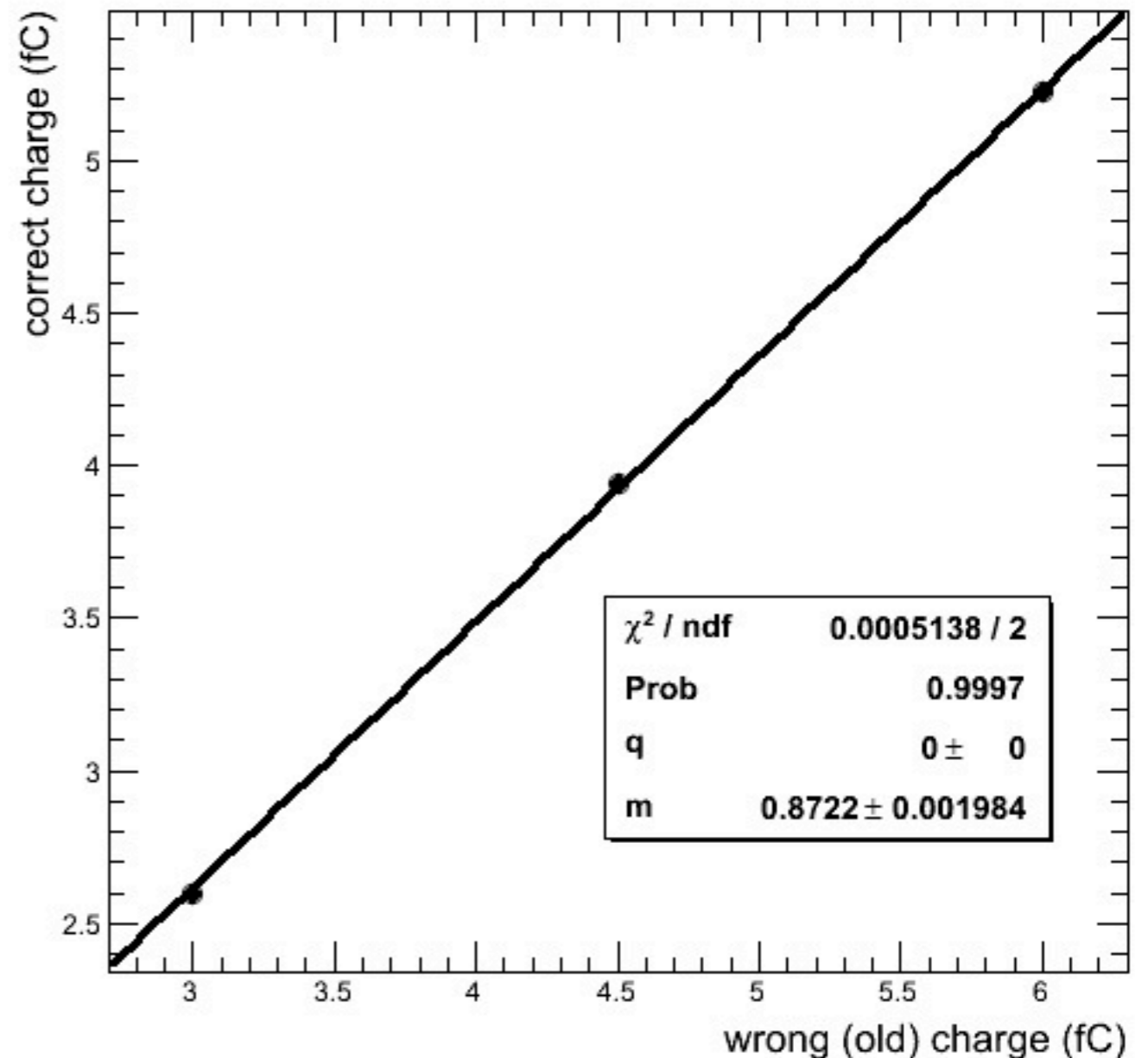
- Characterization of the chip in Lab:
 - Table 1 and the text should be corrected
 - signal-to-noise is 100 (not 200)
- Testbeam Results:
 - the threshold of 770 DAC corresponds to:
 - chip 12 → 6650 e⁻ = 41.6% MIP
 - chip 53 → 6510 e⁻ = 40.7% MIP
 - chip 55 → 6090 e⁻ = 38.1% MIP
 - range of 730 – 820 DAC:
 - chip 12 → 3340 – 10800 e⁻ = 20.9% – 67.5% MIP
 - chip 53 → 3460 – 10500 e⁻ = 21.6% – 66.5% MIP
 - chip 55 → 2670 – 10300 e⁻ = 16.7% – 64.4% MIP
- Simulation:
 - check the values of the charge used to produce the points in Fig. 9 and the charge estimated from Fig. 11.

back-up slides

Charge Scaling

- in the board where the DUTs have been tested we have a correction factor to get the actual ddp applied to the capacitance in the injection runs
- 3 useful points: 3, 4.5, 6 fC
- linear relation extracted with a fit:
 - $y = mx + q$
- fitting function constrained to cross the point (0,0)
- in this presentation, q' stands for the *wrong* charge

real injected charge



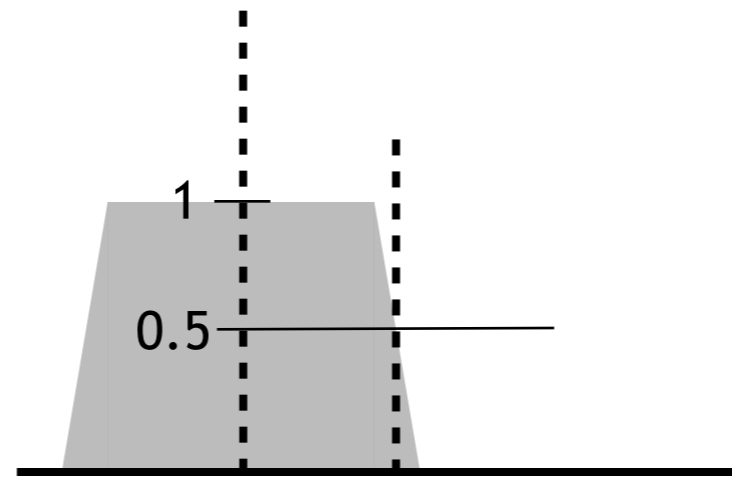
the DUTs

- for each chip we have studied 2/3 ena. For the 128 pixels in each ena we have:
 - inject scans: distribution of the V_{out} at $q' = 3, 4.5, 6$ fC
 - noise scan: distribution of the baseline and of V_{out}
- V_{out} and baseline of each DUT has been evaluated as the average (over the 2/3 ena) of the mean of the distributions (of the pixels of a given ena)

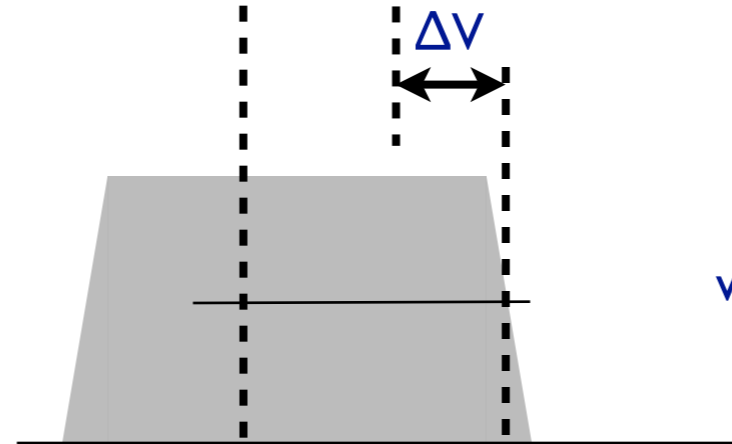
chip	ena	noise run	3 fC run	4.5 fC run	6 fC run
chip19	19	6	8	9	10
	24	7	26	27	28
chip12	6	11	7	8	9
	19	10	3	4	5
	30	12	13	14	15
chip53	6	1	4	5	6
	20	2	7	8	9
	30	3	11	12	13
chip54	6	3	4	5	6
	20	7	8	9	10
	30	11	12	13	14
chip55	6	3	8	9	10
	20	2	4	5	6
	30	7	13	14	15

occupancy curve

noise scan

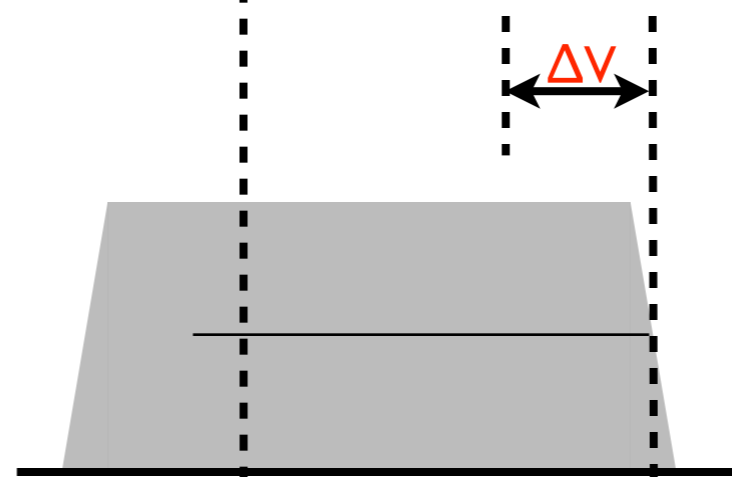


injection scan
with $q = 0$



ΔV = correction applied to
all chips to $V_{out}(0)$ measured
with noise scans instead of inject scans.
Estimated from chip I = +5 DAC.

injection scan
with $q > 0$



$\Delta V/q = \text{gain}(q)$

baseline

V_{out}